

REMARKS

Favorable reconsideration of this application in light of the present amendments and the following discussion is respectfully requested.

Claims 1, 4, and 6 are pending. Claims 2, 3, 5, and 7-9 are canceled from the present application without prejudice. Claims 1, 4, and 6 have been presently amended. Support for the claim amendments are found in the specification on page 24 of the filed English translation.

In the Office Action, Claims 1 and 4 were rejected as being unpatentable over Nishida et al (U.S. Patent No. 6,842,207), Fujimori et al (U.S. Pat. Appl. Publ. No. 2002/0075441), and Yi et al (U.S. Pat. Appl. Publ. No. 2003/0104291). Claim 6 was rejected as being unpatentable over Nishida et al, Fujimori et al, and Yi et al in view of Ochiai et al (U.S. Pat. No. 6,768,531).

Regarding the rejection on the merits, Claim 1 has been clarified to define that: a light shield layer is disposed in a picture-frame shape along a peripheral edge of the display region in which a columnar spacer and the light shield layer are formed simultaneously using a negative-type photosensitive resin material by undergoing a single exposure process through a photo mask having a predetermined pattern, as shown illustratively of the present invention is not disclosed in any of the references.

Yi et al, applied in the Office Action for its teaching of a light shield layer, do not disclose the presently defined light shield layer disposed in a picture-frame shape along a peripheral edge of the display region in which a columnar spacer and the light shield layer are formed simultaneously using a negative-type photosensitive resin material by undergoing a single exposure process through a photo mask having a predetermined pattern. Specifically, Yi et al disclose that a BM and the spacer are formed by a photosensitive black material and

Yi et al disclose that the BM and spacer are formed by a double exposure process. See numbered paragraphs [0037] - [0038] of Yi et al.

Yi et al do not disclose that the BM and spacer are formed both of a negative-type photosensitive resin material by undergoing a single exposure process through the photo mask, as in the presently defined.

As disclosed in the specification on page 27, the simultaneous fabrication of the columnar spacers and the light shield layer provides increased yield, reduced manufacturing costs, and improves support strength, providing distinctions for the examiner's consideration under M.P.E.P. § 2113.

Hence, with no disclosure or suggestion in the applied art for the defined light shield layer, Applicant respectfully submits that Claim 1 and the claims dependent therefrom patentably define over the art of record.

Consequently, in view of the foregoing discussion and present amendment, it is respectfully submitted that this application is in condition for allowance. An early and favorable action is therefore respectfully requested.

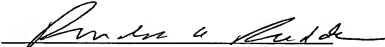
Respectfully submitted,

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